

C1b and
A rotational coupler 114 couples a helium source (not shown) to the lower bellows flange 92b and the pedestal 18. The rotational coupler 114 is coupled to a vented screw 116 that allows helium to pass from the rotational coupler 114 to the hollow lift rod 102b. Thus, the rotational coupler 114 and the vented screw 116 move with the lift rod 102b in response to actuation of the lift actuator 104. The lift rod 102b conveys helium to the coolant chamber 100 and the slots 16a.

WTK
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In the Claims:

Please cancel claim 11 without prejudice or disclaimer of the subject matter thereof.

Please amend claim 10 to read as follows:

Sub A
10. (Twice amended) A method of plasma etching a wafer, said method comprising:

coupling a chuck to a rotatable pedestal, the pedestal comprising a central bore having a hollow shaft disposed therein, the chuck and the pedestal cooperating to define a coolant chamber in fluid communication with the hollow shaft;

coupling the wafer to the chuck;

rotating the pedestal so as to rotate the coupled wafer; and

plasma etching the rotating wafer while cooling the chuck by communicating a coolant through the hollow shaft to the coolant chamber.